Inventor:

Jerome M. Eldridge

Title:

Perovskite-Type Material Forming Methods, Capacitor Dielectric Forming

Methods, and Capacitor Constructions

Assignee:

Micron Technology, Inc.

Docket No.: MI22-2395

INFORMATION DISCLOSURE STATEMENT PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The aboveidentified application is a divisional application of co-pending application Serial No. 10/208,154, filed July 29, 2002. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. § 1.98(d) and MPEP § 609(2).

Citation of these references is respectfully requested.

Respectfully submitted,

Dated:

14 Oct 2003

By:

Reg. No.

Sheet 1 of 2 Priority SERIAL NO. 10/208,154 ATTY, DOCKETNO. U.S. DEPARTMENT OF COMMERCE Form PTO-1449 MI22-2395 PATENT AND TRADEMARK OFFICE APPLICANT LIST OF ART CITED BY APPLICANT Jerome M. Eldridge (Use several sheets if necessary) Priority GROUP Priority FILING DATE U.S. PATENT DOCUMENTS Subclass Filing Date Class Date Document If Appropriate *Examiner Initial Number 9/27/94 Hase et al AA 5,350,738 0919/94 Hase et al 5,350,738 AB 12/1993 Micheli et al AC 5,272,341 Kammerdiner et al 08/1992 ΑD 5,142,437 10/2002 Eldridge ΑE 6,461,931 02/2000 Jeon, Yoo Chan ΑF 6,025,257 08/1998 Chivukula 5,789,268 AG AН ΑI FOREIGN PATENT DOCUMENTS Subclass Translation Class Date Number Yes ΑJ ΑK OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) John Baliga, "New Materials Enhance Memory Performance", Semiconductor International, November 1999, pgs. 1-8. AN "Advances in Ultrathin Oxides and Oxynitrides I", Materials Research Society Symposium Proceedings Series, Vol. 567,, April 5, 1999, 2 pages. ΑO K.S. Tang, W.S. Lau, and G.S. Samudra, "Trends in Dram Dielectrics", IEEE Circuits & Devices, Vol. 13, No. 3, May 1997, pgs. 27-34 ΑP D.W. Hess, "Plasma-assisted oxidation, anodization, and nitridation of silicon", IBM Journal of Research & Development, Vol. 43, No. 1/2, Plasma AQ processing, 22 pages. O. Kubaschewski, E. LL. Evans, "Metallurgical Thermochemistry", Pergamon Press, 1958, pgs. 226-227 and 336-337 AR Ting, Chen, Liu, "Structural evolution and Optical properties of TiO, thin films prepared by thermal oxidation of sputtered Ti films", Journal of AS Applied Physics, Vol. 88, Number 9, 15 October 2000, pgs. 4628-4633.

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Richard A. Swalin, "Thermodynamics of Solids", Second Edition, Chapter 5, John Wiley & Sons, 1972, pgs.112-115.

O. Kubaschewski, B.E. Hopkins, "Oxidation of Metals and Alloys", Butterworths London, Second Edition, 1962, pgs. 36-37 and 70-73.

F.P. Fehlner, "Low-Temperature Oxidation", Monograph published by Electrochemical Society, Pennington, New Jersey, 1983, pgs.31-35.

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Form PTO-1449

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY. DOCKETNO. MI22-1667

SERIAL NO. Filed Herewith

APPLICANT

LIST OF ART CITED BY APPLICANT Jerome M. Eldridge (Use several sheets if necessary) GROUP FILING DATE Unknown Filed Herewith U.S. PATENT DOCUMENTS Filing Date
If Appropriate Class Subclass Name Date *Examiner Document Initial Number 8/29/00 Eldridge (as filed and amended 3/28/02) 09/651,380 AA AB AC ΑD ΑE ΑF AG ΑH ΑI ΑJ ΑK ΑL FOREIGN PATENT DOCUMENTS Subclass Translation Class Country Date Document Number No Yes AM ΑN AO AP AQ OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) AR AS ΑT DATE CONSIDERED **EXAMINER**

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